The impact of O2/N2 ratio in O3 based TiO2-Active layer in Vacancy-modulated conductive oxide

Fig 1. XRD Pattern of the TiO2 stacks as deposited at 210°C and 250°C

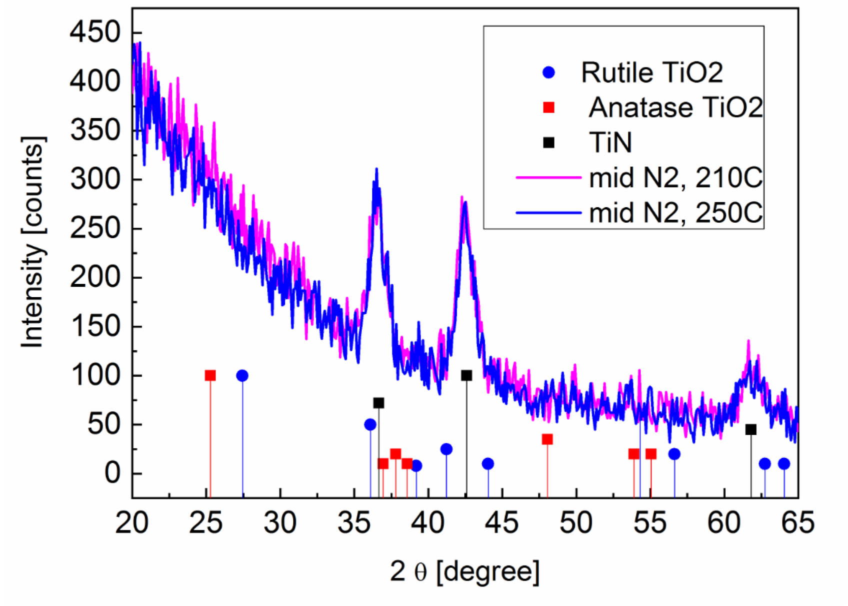

Fig 2. IV curves and VBD, pos of the TiO2 stacks as deposited at 210°C